

ABSTRACT

A vacuum processing apparatus includes a vacuum processing chamber, a base which is provided in the vacuum processing chamber, and on which a substrate to be processed is placed, an exhaust mechanism which exhausts gas from the vacuum processing chamber from a lower side with respect to the base, and an exhaust ring which is annularly formed to surround the periphery of the base. The exhaust ring has a plurality of exhaust holes having different diameters. The diameters of the exhaust holes located in an outer circumferential portion of the exhaust ring are greater than those of the exhaust holes in an inner circumferential portion.